Application No. : 10/666,586

Responsive to an Office Action mailed February 9, 2006 Response filed April 10, 2006

LISTING OF CLAIMS

The following listing of claims is provided as a convenience to the Examiner.

A method for detecting a particle on a substrate, wherein the 1. (Original) substrate is used in the fabrication of an integrated device, the method comprising:

contacting the substrate with a monomer, wherein the particle catalyzes the polymerization of the monomer, and

detecting the particle using a particle counter.

- The method of claim 1, wherein the particle counter detects a 2. (Original) property selected from the group consisting of number of particles, sizes of the particles, positions of the particles, and combinations thereof.
- The method of claim 1, wherein the particle counter is capable of 3. (Original) detecting particles on both sides of the substrate without unmounting the substrate.
- The method of claim 1, wherein the particle counter detects (Original) particles optically.
- The method of claim 4, wherein the particle counter is a (Previously presented) laser scanner.
- 6. (Original) The method of claim 4, wherein the particle counter detects a property selected from the group consisting of absorbance, fluorescence, reflectance, refractive index, and polarization.
- The method of claim 1, wherein the composition of the particle is 7. (Original) identified.
- 8. The method of claim 7, wherein the composition of the particle is (Original) identified by the polymerization rate of the monomer.
- The method of claim 8, wherein the monomer is polymerized by a 9. (Original) plurality of particle types.
- The method of claim 8, further comprising repeating the contacting 10. (Original) and detecting steps.
- The method of claim 1, wherein the substrate is contacted with a 11. (Original) plurality of monomers.

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- 12. (Original) The method of claim 11, wherein a plurality of monomers contact the substrate simultaneously.
- 13. (Original) The method of claim 11, wherein a plurality of monomers contact the substrate sequentially.
 - 14. (Original) The method of claim 1, wherein the particle is a metal.
 - 15. (Original) The method of claim 14, wherein the metal is copper.
 - 16. (Original) The method of claim 1, wherein the substrate comprises silicon.
- 17. (Original) The method of claim 16, wherein the substrate comprises a single crystal silicon wafer.
- 18. (Original) The method of claim 1, wherein the monomer is in the vapor phase.
 - 19. (Original) The method of claim 1, wherein the monomer is an alkene.
- 20. (Original) The method of claim 19, wherein the alkene is selected from the group consisting of styrene, methyl acrylate, ethyl acrylate, methyl methacrylate, and acrylonitrile.
- 21. (Original) The method of claim 1, wherein the monomer is selected from the group consisting of aniline and thiophene.
 - 22. (Original) The method of claim 1, further comprising an initiator.
 - 23. (Original) The method of claim 22, wherein the initiator is benzyl bromide.
- 24. (Original) The method of claim 1, wherein the substrate is irradiated with electromagnetic radiation.
 - 25-51. (Canceled)